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Formation of a nanostructured CrN layer on nitrided tool steel by low-temperature chromizing

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A duplex chromizing process involving the salt bath chromizing of a plasma-nitrided tool steel was carried out at 773 K for 3-24 h. A single-phase CrN layer with a grain size ranging from 20 to 50 nm and an underlying layer consisting of α -Fe and nano-sized CrN grains with a grain size ranging from 40 to 80 nm were formed by a 24 h chromizing at 773 K. The duplex chromizing mechanism was discussed.

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Surface nanocrystallization can be realized in three ways [1]. The first method is based on various surface coating and deposition processes [2,3]. The second method transforms the surface layers of materials into a nanocrystalline structure while keeping the overall composition unchanged [4,5]. The third method is a duplex process in which a nanostructured transformable layer is developed and joined with chemical, thermal or metallurgical processes to produce nanostructured layers with different chemical compositions or different phases [6].

The purpose of this discussion is to report a novel process with which a nanostructured CrN layer can be formed directly on a nitrided steel surface by a low-temperature chromizing process. By this method, a tool steel (AISI H13) was surface nanocrystallized with CrN grains.

The substrate material was a commercial AISI H13 steel containing 0.38C, 5.41Cr, 1.18Mo, 0.94Si, 0.93V, 0.23Mn, and balance Fe (in wt.%). The specimens were vacuum austenized at 1303 K for 1.5 h, oil quenched and tempered at 823 K for 3 h. The heat-treated specimens were then polished with up to 900 grade emery paper, degreased, cleaned and plasma nitrided at 813–833 K for 5.5 h. The plasma-nitrided specimens were finally salt bath chromized at 773 K for 3, 6 and 24 h,

then water quenched. All the specimens concerned were plasma nitrided together in a single batch to ensure an even nitrided layer throughout them. X-ray diffraction of the specimens were conducted using a PHILPS X'Pert MPO Pro X-ray diffractometer with Cu K_{α} radiation. Cross-sectional specimens were etched with 3% Nital and characterized using a LEO1530VP scanning electron microscope (SEM) with a quadrature back-scattering detector. The Cr K_{α 1} and Fe K_{α 1} profiles across the coatings were determined by X-ray energy-dispersive spectroscopy (EDS) and that of N K_{α} was determined by electron probe microanalysis (EPMA). Transmission electron microscopy (TEM) of the cross-sectional foils was carried out with a JEM 2010 transmission electron microscope working at 200 kV.

The back-scattered electron SEM microstructure of the as-plasma-nitrided specimen, shown in Figure 1a, indicates that on the outer surface of the specimen was a compound layer (layer C) consisting mainly of ε iron nitride phase (confirmed by the XRD spectrum shown in Fig. 2). A "cover layer", marked as layer C₀ in Figure 1a, was formed on the outer surface. This cover layer, which was reported [7] to be harmful to the finished coatings, was mechanically removed before the specimens were salt bath chromized. In addition, as clearly revealed by optical microscopy, the nitriding formed a diffusional zone of about 150 µm beneath the compound layer in which the nitrides of the alloying elements were precipitated.

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Figure 1. Cross-sectional microstructures of the coatings on H13 specimens subjected to various treatments. (a) Specimen plasma nitrided for 5.5 h at 813–833 K, SEM back-scattered electron image; (b) specimen first plasma nitrided and then chromized for 6 h at 773 K, SEM back-scattered electron image; (c) EDS profiles of Cr $K_{\alpha 1}$ and Fe $K_{\alpha 1}$ along the line marked in (b); (d) specimen first nitrided and then chromized for 24 h at 773 K, SEM back-scattered electron image; (e) EDS profiles of Cr $K_{\alpha 1}$ and Fe $K_{\alpha 1}$ along the line marked in (d).



Figure 2. XRD patterns showing the phase structure evolutions in the near-surface layer during the duplex chromizing process for the asnitrided specimen, and the specimens first nitrided and then chromized for 3, 6 and 24 h respectively.

As shown in Figure 1b and d, a complete chromized layer, consisting of three sublayers, C_1 , D and C_2 , was

formed within, and at the expense of, the former compound layer formed by nitriding, marked as layer C in Figure 1a. Here, sublayer C_1 is a chromized compound layer consisting of single-phase CrN, sublayer D is a mixture of CrN and α-Fe, and sublayer C2 consists mainly of γ' -Fe₄N. Sublayer (D + C₂), also named the diffusional layer of chromizing, became a single layer D with the layer C_2 having disappeared as the chromizing time was increased from 6 h (Fig. 1b) to 24 h (Fig. 1d). It was found that the chromized layer as a whole became thicker as the chromizing time was prolonged, thus leading to a chromized layer thickness larger than that of the original nitrided compound layer, whereas the chromized compound layer C1, having been formed quickly in the early stages of chromizing, remained nearly unchanged in thickness with increasing chromizing time. For example, the original nitrided compound layer C in Figure 1a, while splitting into the three sublayers C_1 , D and C_2 during chromizing, was thickened from about 12 to 23 µm during a 24 h chromizing at 773 K, with the chromized compound layer C_1 having a constant thickness of 3–4 μ m.

The XRD patterns in Figure 2 show that the intensity of the nitriding-formed ε -Fe₂N and γ' -Fe₄N phases is decreased, while that of the CrN phase is increased, with prolonged chromizing duration, and that the ε -Fe₂N in the original nitrided compound was nearly completely consumed during a 6 h chromizing, with only γ' -Fe₄N remaining, whereas both ϵ -Fe₂N and γ' -Fe₄N were present in the as-nitrided compound layer. A comparison of the light contrast of layer C₂ with the darker contrast of layer D in the back-scattered electron SEM image shown in Figure 1b suggests that layer C2 contained none of the α -Fe that was detected to be present in layer D and assumed to be produced via reaction (6), and that the release of nitrogen atoms [N] from the ε -Fe₂N during chromizing would follow the following reaction in which no α -Fe was produced:

$$2\varepsilon - Fe_2 N \to \gamma' - Fe_4 N + [N] \tag{1}$$

The nitrogen atoms [N] so released from ε -Fe₂N could be consumed during chromizing in three possible ways: (i) they diffuse outward to the surface and react with the incoming Cr atoms to form chromium nitrides; (ii) they recombine with each other to form N₂; and (iii) they diffuse inward to transform the adjacent substrate (previous supersaturated with nitrogen during plasma nitriding) into iron nitrides. With [N] atoms diffusing outward, a dense layer consisting of single-phase CrN (marked as layer C₁ in Fig. 1b) was formed on the surface layer of the specimen via the reaction

$$[N] + [Cr] \to CrN, \tag{2}$$

where [Cr] represents the activated chromium atoms provided by the chromizing salt bath. The [N] and [Cr] atoms diffused in opposite directions in the ϵ -Fe₂N layer and combined to form CrN.

The diffusion process may, however, be slowed down somewhere in the interior of the ε -Fe₂N layer close to the surface, since the path taken by the [N] atoms diffusing to the surface and reacting there with the incoming [Cr] atoms would be too long to sustain reaction (2). Download English Version:

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